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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/056,179	01/22/2002	Theodore M. Taylor	MI22-1824	-1824 9467		
21567	7590 12/11/2002					
WELLS ST. JOHN ROBERTS GREGORY & MATKIN P.S.			EXAMINER			
601 W. FIRST SUITE 1300		WEISS, HOWARD				
SPOKANE, WA 99201-3828			ART UNIT	PAPER NUMBER		
			2814			
			DATE MAILED: 12/11/2002			

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No. Applica		Applicant(s)	it(s)		
	10/056,179		TAYLOR, THEODORE, M.			
Office Action Summary	Examiner		Art Unit	Th		
	Howard Weiss		2814			
The MAILING DATE of this communication app Period for Reply	ears on the cover	sheet with the co	rrespondence a	address		
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, - Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however within the statutory mining will apply and will expire Society cause the application to	er, may a reply be time num of thirty (30) days v X (6) MONTHS from th become ABANDONED	ly filed will be considered tin e mailing date of this (35 U.S.C. § 133).	,		
itatus						
1) Responsive to communication(s) filed on 19 S						
,	is action is non-fin					
3) Since this application is in condition for allowated closed in accordance with the practice under a disposition of Claims	•	•		1. (1)		
4) Claim(s) 50-56,58,59 and 62-68 is are pending	g in the application	١.		for failir		
4a) Of the above claim(s) is/are withdraw	vn from considera	tion.		required		
5) Claim(s) is/are allowed.				1 1		
6) Claim(s) 50-56,58,59 and 62-68 is/are rejected						
7) C aim(s) is/are objected to.				•		
8) Claim(s) are subject to restriction and/or	r election requiren	nent.		<u> [2 (%)</u>		
application Papers						
9) The specification is objected to by the Examine	r.			ifincə 🖽 🕆		
10) The drawing(s) filed on is/are: a) accept	oted or b) objecte	d to by the Exam	iner.			
Applicant may not request that any objection to the						
11) The proposed drawing correction filed on	is: a) approved	d b) disapprov	ed by the Exam	. <del></del>		
If approved, corrected drawings are required in rep		on.		118 100		
12) The oath or declaration is objected to by the Ex	aminer.		•			
riority under 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreign	priority under 35	U.S.C. § 119(a)-	·(d) or (f).			
a) All b) Some * c) None of:			· -			
1. Certified copies of the priority documents	s have been recei	ved.	•			
2. Certified copies of the priority documents	s have been recei	ved in Applicatio	n No			
<ul> <li>3. Copies of the certified copies of the prior application from the International But</li> <li>* See the attached detailed Office action for a list</li> </ul>	reau (PCT Rule 1	7.2(a)).		al Stage		
14) Acknowledgment is made of a claim for domestic	c priority under 35	U.S.C. § 119(e)	(to a provision	nal application).		
a) The translation of the foreign language pro	• •					
ttachment(s)						
Notice of References Cited (PTO-892)  Notice of Draftsperson's Patent Drawing Review (PTO-948)  Information Disclosure Statement(s) (PTO-1449) Paper No(s) 8	5)	Interview Summary ( Notice of Informal Pa Other:	•			
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Application/Control Number: 10/056,179

Art Unit: 2814

Attorney's Docket Number: MI22-1824

Filing Date: 1/22/02

Continuing Data: none

Claimed Foreign Priority Date: none

Applicant(s): Taylor

**Examiner: Howard Weiss** 

# Claim Objections

1. Claim 63 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim. The Applicant is required to cancel the claim(s), or amend the claim(s) to place the claim(s) in proper dependent form, or rewrite the claim(s) in independent form. Claim 63 states that the floating gate only partially fills the region. However, Claim 65 states that the floating gate completely fills the region. Since a dependent claim (i.e. Claim 63) has all the limitations on the claims from which it depends (i.e. Claim 65), these limitations are in conflict with each other. Please see MPEP 608.01(n) II.

### Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 50, 52, 53 to 56 and 64 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yu et al. (U.S. Patent No. 6,376,877) and Shirai et al. (IEDM 1995).

Yu et al. show most aspects of the instant invention (e.g. Figure 7A) including:

> a semiconductive substrate 102

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- a pair of STI masses 316A, 317A with first portions within the substrate and second portions projecting outwardly from the substrate and having first WF and second W<sub>C</sub> cross-sectional dimensions where W<sub>C</sub> > W<sub>F</sub>
- a first dielectric layer 306A
- a floating gate 308A with a concave upper surface and which does not fill the region between the second portions of said STI masses
- a second dielectric layer 310A and a control gate 312A

Yu et al. does not show the rugged outermost surface of said floating gate being were made of hemispherical grain polysilicon (HSG Poly-Si). Shirai et al. teach (e.g. see being to pro-Abstract) to roughen up the outer surface of a floating gate using HSG Poly-Si to (IEDM 190 increase the capacitive-coupling ration of the memory cell. It would have been obvious to a person of ordinary skill in the art at the time of invention to roughen up the outer surface of a floating gate using HSG Poly-Si as taught by Shirai et al. in the device of Yu et al. to increase the capacitive-coupling ration of the memory cell.

4. Claims 51, 52, 54, 58, 62, 65, 66 and 69 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ding et al. (U.S. Patent No. 6,214,667) and Shirai et al. (IEDM 1995).

Ding et al. show most aspects of the instant invention (e.g. Figure 2F) including

- a semiconductive substrate 200
- a pair of STI masses 214, 216 with first portions within the substrate and second portions projecting outwardly from the substrate and having first and second cross-sectional dimensions which are essentially equal
- a first dielectric layer 204
- a floating gate 222a with a concave upper surface and which fills the region between the second portions of said STI masses
- a second dielectric layer 224 and a control gate 226

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Ding et al. do not show the rugged outermost surface of said floating gate being made of hemispherical grain polysilicon (HSG Poly-Si). Shirai et al. teach (e.g. see Abstract) to roughen up the outer surface of a floating gate using HSG Poly-Si to increase the capacitive-coupling ration of the memory cell. It would have been obvious to a person of ordinary skill in the art at the time of invention to roughen up the outer surface of a floating gate using HSG Poly-Si as taught by Shirai et al. in the device of Ding et al. to increase the capacitive-coupling ration of the memory cell.

5. Claims 50, 52 to 54, 58, 59, 63, 64 and 67 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hsieh et al. (U.S. Patent No. 6,153,494) and Shirai et al. (IEDM 1995).

Hsieh et al. show most aspects of the instant invention (e.g. Figure 3e) including:

- a semiconductive substrate 100
- a pair of STI masses 240, 250 with first portions within the substrate and second portions projecting outwardly from the substrate and having first and second cross-sectional dimensions which are essentially equal
- a first dielectric layer 260
- a floating gate 270 with a concave upper surface and which does not fill the region between the second portions of said STI masses
- > a second dielectric layer 280 and a control gate 290

Hsieh et al. do not show the rugged outermost surface of said floating gate being made of hemispherical grain polysilicon (HSG Poly-Si). Shirai et al. teach (e.g. see Abstract) to roughen up the outer surface of a floating gate using HSG Poly-Si to increase the capacitive-coupling ration of the memory cell. It would have been obvious to a person of ordinary skill in the art at the time of invention to roughen up the outer surface of a floating gate using HSG Poly-Si as taught by Shirai et al. in the device of Hsieh et al. to increase the capacitive-coupling ration of the memory cell.

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The Examiner notes that Claim 63 is included in this art rejection because Hsieh et al. teaches the limitation of the floating gate partially filling the region. As noted above, the limitations in Claim 63 conflict with Claim 65 from which it depends.

#### Response to Arguments

6. The Applicant's arguments filed 9/19/02 have been fully considered but they are not persuasive. The Applicant states that the teachings of Shirai et al. cannot be combined with the other references since Shirai et al. uses LOCOS isolation not STI. However, the LOCOS isolations used in Shirai et al. are exemplary and the use of STI is not excluded as stated by the Applicant. For a reference to teach away form another reference, it must explicitly or otherwise specifically exclude the features and / or limitations described. Shirai et al. only mention LOCOS isolation in the one sentence as pointed out by the Applicant. No mention is made anywhere else in the PSINCHE: E Article concerning how the device is isolated.

In response to the Applicant's argument that there is no suggestion to combine the references, the examiner recognizes that obviousness can only be established by combining or modifying the teachings of the prior art to produce the claimed invention where there is some teaching, suggestion, or motivation to do so found either in the references themselves or in the knowledge generally available to one of ordinary skill in the art. See In re Fine, 837 F.2d 1071, 5 USPQ2d 1596 (Fed. Cir. 1988) and In re Jones, 958 F.2d 347, 21 USPQ2d 1941 (Fed. Cir. 1992). In this case, the motivation to combine the teachings of Shirai et al. (i.e. to roughen up the outer surface of a floating gate using HSG Poly-Si) is found in the Abstract (i.e. to increase the capacitive-coupling ration of the memory cell).

In view of these reasons and those set forth in the present office action, the rejections of the stated claims stand.

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#### Conclusion

- 7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Mori et al. (U.S. Patent Application Pub. No. 2002/0093073), Sakamoto et al. (U.S. Patent No. 6,459,121) and Yu et al. (U.S. Patent No. 6,448,606) teach similar devices as the instant invention.
- 8. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

- 9. Papers related to this application may be submitted directly to Art Unit 2814 by facsimile transmission. Papers should be faxed to Art Unit 2814 via the Art Unit 2814 Fax Center located in Crystal Plaza 4, room 3C23. The faxing of such papers must conform with the notice published in the Official Gazette, 1096 OG 30 (15 November 1989). The Art Unit 2814 Fax Center number is (703) 308-7722 or -7724. The Art Unit 2814 Fax Center is to be used only for papers related to Art Unit 2814 applications. The official TC2800 Before-Final, (703) 872-9318, and After-Final, (703) 872-9319, Fax numbers will provide the fax sender with an auto-reply fax verifying receipt of their fax by the USPTO.
- 10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Howard Weiss at (703) 308-4840 and between the

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hours of 8:00 AM to 4:00 PM (Eastern Standard Time) Monday through Friday or by e-mail via **Howard.Weiss@uspto.gov**.

Any inquiry of a general nature or relating to the status of this application should be directed to the Group 2800 Receptionist at (703) 308-0956.

11. The following list is the Examiner's field of search for the present Office Action:

Field of Search		)at		
U.S. Class / Subclass(es): 257/317, 510	thru 12/4	/02	J K	US-
Other Documentation: none		-	L	US-
Electronic Database(s): EAST		1/02		US

HW/hw 4 December 2002 Howard Weiss Examiner Art Unit 2814

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